

February 1, 2002

TO: Commissioner of Patents and Trademarks
Washington, D.C. 20231

#3/a

FROM: George O. Saile, Reg. No. 19,572
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SUBJECT: **Reissue Application of:**
Patent #: 6,019,906
Issue Date: Feb. 1, 2000
Inventor: Syun-Ming Jang, Ming-Hsin Huang
Examiner:
Art Unit:
Title: Hard Masking Method for Forming Patterned Oxygen
Containing Plasma Etchable Layer

PRELIMINARY AMENDMENT

This regards the Reissue Application of the above identified patent. Please amend
the above-identified patent as follows:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States
Postal Service as first class mail in an envelope addressed to: Commissioner of
Patents and Trademarks, Washington, D.C. 20231 on February 1, 2002.

Signature 
Stephen B. Ackerman, Reg. No. 37,761

Date: 2/1/02